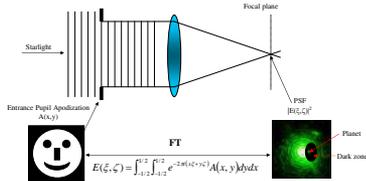


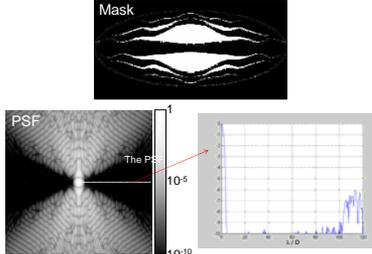
SHAPED PUPIL CONCEPT

Pupil Apodization Overview



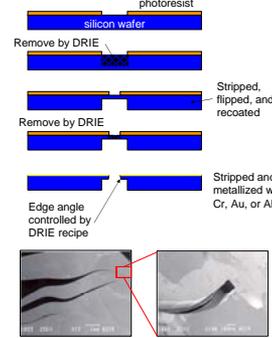
- Can design PSFs by apodizing the pupil
- Use nonlinear optimization to find $A(x,y)$ for desired PSF
- Optimization metrics
 - Inner and outer working angles (IWA and OWA)
 - contrast
 - throughput

Our Current Mask



- Designed for elliptical TPF primary shape
- IWA = $4 \lambda/D$ in 45° arc, throughput (airy) = 30%
- Simpler to manufacture and less polarization sensitivity than e.g. barcode masks
- Central obstruction can be used for secondary

Mask Manufacture



- Manufactured by JPL
- Commercial Si wafer
- Double-sided Deep Reactive Ion Etch (DRIE) to make holes
 - First etch: wafer thinned to 50 micron thickness around openings
 - Second etch: through etch to complete holes
 - Optional thin metal coating
- Mask size 25mm and 10mm
- Efficient, repeatable process

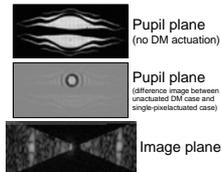
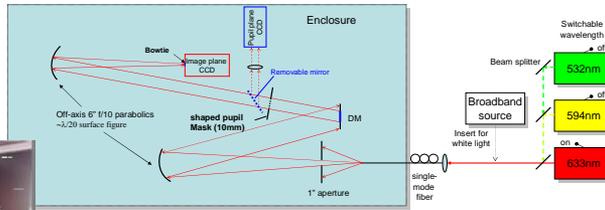
THE TPF@PRINCETON LAB

Inside the Lab



- Clean room
- 1.2 x 5 m vibration-isolated optical bench
- Enclosure to eliminate thermal convection, air turbulence, particulate contamination, and stray light

Optical Layout Schematic

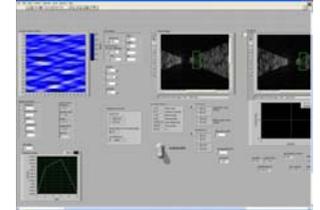


- Can select from any combination of 3 laser wavelengths, or insert a broadband white light source (halogen lamp)
- Single mode fiber creates a simulated star
- First parabolic brings the star out to infinity
- DM has 32x32 actuators, 10mm aperture, made by Boston Micromachines
- Removable mirror can be used to see the pupil plane
- Second parabolic focuses the light onto the CCD
- Image-plane mask (bowtie mask) placed on CCD chip to block bright portions of the PSF

Algorithm: Speckle Nulling

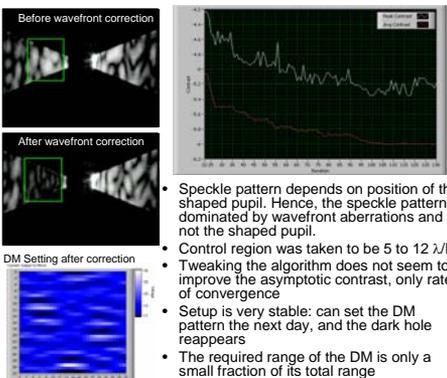
- Algorithm:
- Look for the brightest pixel in the dark zone
 - Compute a DM ripple that would place a speckle centered on that pixel
 - Find phase which minimizes that pixel
 - Update DM
 - Repeat

Computer Interface for interactive and automatic speckle nulling



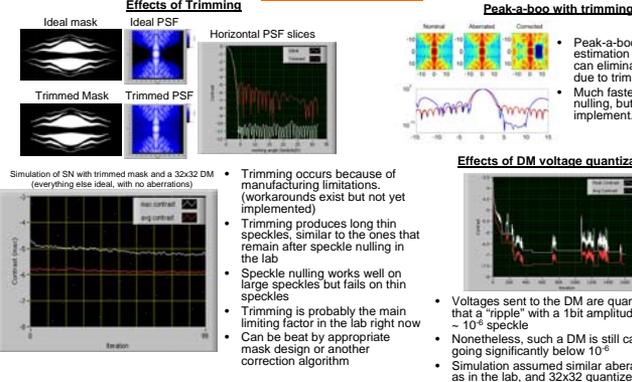
RESULTS

Typical Experimental SN Run



- Speckle pattern depends on position of the shaped pupil. Hence, the speckle pattern is dominated by wavefront aberrations and not the shaped pupil.
- Control region was taken to be 5 to 12 λ/D
- Tweaking the algorithm does not seem to improve the asymptotic contrast, only rate of convergence
- Setup is very stable: can set the DM pattern the next day, and the dark hole reappears
- The required range of the DM is only a small fraction of its total range

Simulations



Contrast Roadmap

Contrast @ $4\lambda/D$	Effects and Milestones
$>10^{-2}$	Airy pattern
$>10^{-4}$	Core of PSF saturates, camera blooms
$>10^{-5}$	Contrast with unactuated DM (1" SP) and 1/20 optics Measured on Princeton testbed, w/o WF corrections (Jan 2005) Measured on Princeton testbed, w/o WF corrections (Sep 2006)
$>10^{-6}$	15 micron trimming for 10mm ripple1 Speckle nulling with 10mm ripple1 on Princeton testbed (Sep 2006) Light thrown into dark zone by BMC DM quilling orders
$>10^{-7}$	Contrast with commercial optics for 2mm SPs Amplitude errors start appearing for 1" SPs at HCT
$>10^{-8}$	DM quilling saturates, need to block with star occulter CCD/occulter reflections if they are in the same plane and occulter isn't perfect (?) Air (?) Trimming of 1" ripple3 Speckle nulling with 25mm ripple3 (Princeton experiment at HCT) in monochromatic and broadband light (Feb 2006)
$>10^{-9}$	Dust in Princeton testbed (?) Thermal stability of DM w/o thermal control (?)
$>10^{-10}$	Mechanical stability of testbed (?) Electronic noise (?) DM precision (?)

CONCLUSIONS

- Shaped pupils are a promising technology for high-contrast imaging
- Initial runs of speckle-nulling-based wavefront correction achieved contrast of 10^{-6}
- Simulations show that the limiting factor is the inability of speckle nulling to correct for mask trimming
- Two ways of overcoming this limit: better mask (less affected by trimming), or better estimation algorithm (such as peak-a-boo).